IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Koji NOZAKI et al. Group Art Unit: 1795

Application Number: 10/623,679 Examiner: Amanda C. Walke

Filed: July 22, 2003 Confirmation Number: 5083

For: RESIST PATTERN THICKENING MATERIAL, RESIST

PATTERN AND PROCESS FOR FORMING THE SAME, AND

SEMICONDUCTOR DEVICE AND PROCESS FOR

MANUFACTURING THE SAME

Attorney Docket Number: 030891 Customer Number: 38834

AMENDMENT UNDER 37 C.F.R. § 1.116 EXPEDITED PROCESSING REQUESTED DO NOT ENTER: /ACW/

11/03/2008

MAILSTOP: AF

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450 October 30, 2008

Sir:

This paper is filed in response to the Office Action dated May 30, 2008, the response due date extended to October 30, 2008 by a two-months Extension of Time.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 12 of this paper.